



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: N.B. Cobb et al.

Attorney Docket No.: MEGC121796

Application No.: 10/698,596

Group Art Unit: 1756

Filed: October 31, 2003

Title: SITE CONTROL FOR OPC

INFORMATION DISCLOSURE STATEMENT

Seattle, Washington 98101

March 11, 2004

TO THE COMMISSIONER FOR PATENTS:

Applicants are aware of the information listed in the attached form that may be material to the prosecution of the above-identified patent application.

1. Copies of the listed publications and other information are enclosed for the Examiner's use.
2. Pursuant to 37 C.F.R. § 1.97(b), this Information Disclosure Statement is being filed within three months of the filing date of the national application (other than a CPA), within three months of the date of entry of the national stage as set forth in 37 C.F.R. § 1.491 in an international application, before the mailing date of a first Office Action on the merits, or before the mailing date of a first Office Action after the filing of an RCE.
3. The Commissioner is hereby authorized to charge any fees under 37 C.F.R. §§ 1.16, 1.17 and 1.18 which may be required during the entire pendency of the application, or credit any overpayment, to Deposit Account No. 03-1740. This authorization also hereby includes a request for any extensions of time of the

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CHRISTENSEN O'CONNOR JOHNSON KINDNESS™
1420 Fifth Avenue
Suite 2800
Seattle, Washington 98101
206.682.8100

appropriate length required upon the filing of any reply during the entire prosecution of this application.

Respectfully submitted,

CHRISTENSEN O'CONNOR
JOHNSON KINDNESS^{PLLC}



Rodney C. Tullett
Registration No. 34,034
Direct Dial No. 206.695.1730

I hereby certify that this correspondence is being deposited with the U.S. Postal Service in a sealed envelope as first class mail with postage thereon fully prepaid and addressed to Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on the below date.

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1420 Fifth Avenue
Suite 2800
Seattle, Washington 98101
206.682.8100

INFORMATION CITED BY APPLICANTS THAT MAY BE MATERIAL TO THE
PROSECUTION OF THE SUBJECT APPLICATION

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U.S. PATENT DOCUMENTS

*Examiner Initials	Cite No.	Document No.	Kind Code	Date (mm/dd/yyyy)	Name
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_____	U2	5,502,654		03/26/1996	Sawahata
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_____	U4	5,723,233		03/03/1998	Garza et al.
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 1420 Fifth Avenue
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U21	6,453,457	B1	09/17/2002	Pierrat et al.
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U23	6,499,003	B2	12/24/2002	Jones et al.

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*Examiner Cite Initial	No.	Document No.	Kind Code	Publication Date (mm/dd/yyyy)	Country	English
						Abstract Provided
	F1	09319067	A	12/12/1997	JP	x
	F2	WO 01/65315	A2	09/07/2001	WO	

OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, Etc.)

*Examiner Cite Initial	No.	
	O1	Cobb, N., and Y. Granik, "Model-Based OPC Using the MEEF Matrix," <i>Proceedings of SPIE, Vol. 4889: 22nd Annual BACUS Symposium on Photomask Technology</i> , Monterey, Calif., Sept. 30-Oct. 4, 2002, p.147.
	O2	Cobb, N., and A. Zakhor, "Experimental Results on Optical Proximity Correction With Variable Threshold Resist Model," <i>Proceedings of SPIE, Vol. 3051: Symposium on Optical Microlithography X</i> , Santa Clara, Calif., Mar. 10-14, 1997, pp. 458-468.
	O3	Cobb, N., and A. Zakhor, "Fast, Low-Complexity Mask Design," <i>Proceedings of SPIE, Vol. 2440: Symposium on Optical/Laser Microlithography VIII</i> , Santa Clara, Calif., Feb. 22-24, 1995, pp. 313-327.
	O4	Cobb, N., and A. Zakhor, "Fast Sparse Aerial Image Calculation for OPC," <i>Proceedings of SPIE, Vol. 2621: 15th Annual BACUS Symposium on Photomask Technology and Management</i> , Santa Clara, Calif., Sept. 20-22, 1995, pp. 534-545.
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Suite 2800
Seattle, Washington 98101
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Examiner

Date Considered

*Examiner: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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1420 Fifth Avenue
Suite 2800
Seattle, Washington 98101
206.682.8100